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Conductors

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## Sommario/riassunto

A wealth of information in one accessible book. Written by international experts from multidisciplinary fields, this in-depth exploration of oxide ultrathin films covers all aspects of these systems, starting with preparation and characterization, and going on to geometrical and electronic structure, as well as applications in current and future systems and devices. From the Contents: Synthesis and Preparation of Oxide Ultrathin FilmsCharacterization Tools of Oxide Ultrathin FilmsOrdered Oxide Nanostructures on Metal SurfacesUnusual Properties of

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